Docket Number: 081468-0302644
Client Reference: P-1698.000-US

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of
FLAGELLO ET AL.

Group Art Unit: 2854

Application No.: 10/698,012

Examiner: Unassigned

Filed: October 31, 2003

Confirmation No.: 7154

For: LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 CFR 1.56, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached PTO-1449. Unless otherwise indicated herein, one copy of each reference is attached. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom. Applicants respectfully request the Examiner return an initialed copy of the enclosed Form PTO-1449 to Applicants with the next Office Communication to indicate that the references have been considered, per MPEP § 609.

The undersigned notes that copies of U.S. references are not required in Information Disclosure Statements (IDS's) in applications filed after June 30, 2003. WO99/49504, submitted with the application on October 31, 2003, is being resubmitted with a translation.

This IDS is being filed (a) within three months of the U.S. filing date of this non-CPA application, or (b) before the mailing date of the first Office Action on the merits in the present application. No certification or fee is required.

Respectfully Submitted,

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Date: March 24, 2004

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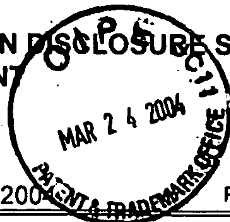
FORM PTO-1449 (modified) To: U.S. Department of Commerce (PW FORM PAT-1449) Patent and Trademark Office	Atty. Dkt. No.	M# 0302644	Client Ref. P-1698.000-US

INFORMATION DISCLOSURE STATEMENT BY APPLICANT



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Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
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	BR	6,600,547 B2	07/2003	Watson et al.	355	30	
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							Enclosed	No	Enclose	No
	OR	WO 2004/019128 A2	03/2004	WIPO	Omura et al.		X			
	PR	JP 58-202448	11/1983	Japan	Yoshio et al.		X			
	QR	WO99/49504	09/1999	WIPO	Fukami et al.		X		X	
	RR	WO 03/077036 A1	09/2003	WIPO	Schuster		X			
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	TR	EP 0418427 A2	03/1991	Europe	MIyake		X			
	UR	EP 1039511 A1	09/2000	Europe	Hirukawa et al.		X			
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	YR	S. Owa et al., "Potential performance and feasibility of immersion lithography," NGL Workshop 2003, July 10, 2003	X			
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Examiner	Date Considered:

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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	KKR						
	LLR						
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							Enclosed	No	Enclose	No
	NNR	JP 62-65326	03/1987	Japan	Noboru		X			
	OOR	JP 62-121417	06/1987	Japan	Koji		X			
	PPR	JP 63-157419	06/1988	Japan	Mamoru		X			
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	SSR	JP 6-124873	05/1994	Japan	Kazuo		X		X	
	TTR	JP 7-220990	08/1995	Japan	Hiroshi et al.		X			
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	WWI	JP 10-303114	11/1998	Japan	Kyoichi		X		X	

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	XXR	M. Switkes et al., "Immerson Lithography at 157 nm," J. Vac. Sci. Technol. B., Vol. 19, No. 6, Nov./Dec. 2001, pp. 2353-56	X			
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	ZZR	B. J. Lin, "Drivers, Prospects, and Challenges for Immersion Lithography," tsmc, Inc., Sept. 2002	X			

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	AAAI						
	BBBI						
	CCC						
	DDD						
	EEEI						
	FFFF						
	GGG						
	HHH						
	IIIR						
	JJJR						
	KKKI						
	LLLF						
	MMN						
	NNN						

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	OOO	JP 10-340846	12/1998	Japan	Taketo		X		X	
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	XXXI	B.J. Lin, "Proximity Prnting Through Liquid," IBM Technical Disclosure Bulletin, Vol. 20, No. 11B, April 1978, p. 4997	X			
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	ZZZF	G.W.W. Stevens, "Reduction of Waste Resulting from Mask Defects," Solid State Technilogy, August 1978, Vol. 21 008, pp. 68-72	X			
	AAA	T. Matsuyama et al., "Nikon Projection Lens Update," Nikon Corporation, (date unknown)	X			

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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	BBB						
	CCC						
	DDD						
	EEE						
	FFF						
	GGG						
	HHH						

FOREIGN PATENT DOCUMENTS

		Document Number	Date MM/YYYY	Country	Inventor Name		English Abstract Enclosed	English Abstract No	Translation Readily Available Enclose	Translation Readily Available No
	IIII									
	JJJ									
	KKK									
	LLL									
	MMM									
	NNN									
	OOO									
	PPP									

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	RRR	Nikon Precision Europe GmbH, "Investor Relations – Nikon's Real Solutions", May 15, 2003	X			
	SSS	H. Kawata et al., "Optical Projection Lithography using Lenses with Numerical Apertures Greater than Unity," Microelectronic Engineering 9 (1989), pp. 31-36	X			
	TTT	J.A. Hoffnagle et al., "Liquid Immersion Deep-Ultraviolet Interferometric Lithography," J. Vac. Sci. Technol. B., Vol. 17(6), Nov/Dec 1999	X			
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	VVV	H. Kawata et al., "Fabrication of 0.2μm Fine Patterns Using Optical Projection Lithography with an Oil Immersion Lens," Jpn. J. Appl. Phys. Vol. 31 (1992), pp. 4174-4177	X			
	WWW	G. Owen et al., 1/8μm Optical Lithography," J. Vac. Sci. Technol. B., Vol. 10, No. 6, Nov/Dec. 1992, pp. 3032-3036	X			
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